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Solution-Processed Thermal-Stable Amorphous Films of Small Molecular Hole Injection/Transport Bi-functional Materials and its Application in High Efficient OLEDs

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Xiaoming Zhao^{a,b}, Shirong Wang^{*a,b}, Jing You^{*a,b}, Yuteng Zhang^{a,b} and Xianggao Li^{a,b}

A series of novel triphenylamine-based small molecular hole transport materials (HTMs) are reported for solution processed organic light-emitting devices (OLEDs). The character of this series of HTMs, denoted as TPD(BTPA)_n (n=1,2,4) is connecting the flexible moieties of butadiene bridged triphenylamine (BTPA) to the *N,N,N',N'*-tetraphenyl-[1,1'-biphenyl]-4,4'-diamine (TPD). The glass transition temperature and crystallization temperature (T_g and T_c) showed an proportional relationship with the number of BTPA moieties. The T_g of TPD(BTPA)₄ can be up to 125.5°C, which is the higher than most of reported small molecular HTMs (T_g : 54°C-116°C). The TPD(BTPA)₄ spincoated film showed an outstanding thermal stability which maintained amorphous even annealed with 110°C, for 48 h. This indicated the break of planar molecular structure with BTPA moieties can suppress the intermolecular stacking. The solution processed OLEDs with 8-Hydroxyquinoline aluminum (Alq₃) as emission and electron transport layer showed high stability at high operation current (> 400 mA cm⁻²). The OLED with TPD(BTPA)₄ achieved a maximum current efficiency of 5.83 cd A⁻¹ (at the operation current density > 400 mA cm⁻²), which is higher than the maximum current efficiency of most evaporation and solution processing OLEDs in identical structure.

1 Introduction

Organic light-emitting devices (OLEDs) are regarded as the next generation flat-panel displays because of advantages, such as portable, full colored, glare free, flexible, short response time, wider viewing angles *etc.*¹⁻³

To date, there mainly are two issues need to be solved about small molecular OLEDs. First, the ultra-thin films in OLEDs are typically fabricated by vacuum evaporation (VE), which has demerits of high energy consuming, waste of materials and unfriendly to environment.⁴ Secondly, the charge transfer and injection require homogeneous interface and layer, which means that the organic semiconductor film should be amorphous form.⁵

The first problem can be solved through solution processing techniques such as layer-by-layer spin coating and ink jet.⁶ While, those techniques are mainly applied in the polymer materials. However, the research on structure-functional relationship of small molecular materials is more mature than the polymers.⁷ Functional characteristics such

as energy level of the polymers depends on not only the unit structure, but also the length of polymer chain which is not a constant.⁸⁻¹⁰ It is believed that the design, synthesis and purification of small molecular materials are more convenient.

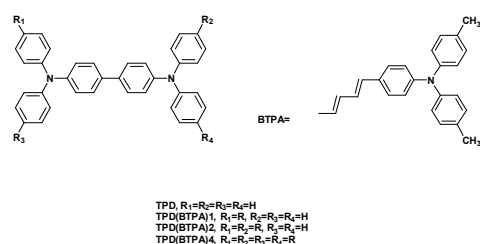
For the second problem, the crystallization of small molecular materials during film-forming in the solution process and operating at high temperature are main obstacles for its application in OLEDs.¹¹⁻¹⁴ The low glass transition and crystallization temperatures (T_g and T_c) lead to formation of polycrystalline in films resulting from thermal stress.¹⁵ In the research reported by Douglas E Loy *et al.*, the OLED with *N,N,N',N'*-tetraphenyl-[1,1'-biphenyl]-4,4'-diamine (TPD) and *N,N'*-diphenyl-*N,N'*-bis-(1-naphthyl)-1,1'-biphenyl-4,4'-diamine (NPD) as HTL showed irreversible failure when heated at 100 and 110°C due to crystallization.¹⁶ As reported, the T_g and T_c of organic semiconductor are determined by the molecular structure. Larger molecular volume resulted in higher T_g .¹⁷⁻¹⁹

^a Department of Applied Chemistry, School of Chemical Engineering and Technology, Tianjin University, Tianjin 300072, China. E-mail: Youj1983@tju.edu.cn

^b Collaborative Innovation Center of Chemical Science and Engineering (Tianjin), Tianjin 300072, China. E-mail: wangshirong@tju.edu.cn

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1 In this work, we designed and synthesized three new
2 HTMs based on the TPD, which has a HOMO level of -5.30 eV
3 and a T_g of 69 °C.^{20, 21} The TPD is modified with different
4 numbers of 4-(penta-1,3-dien-1-yl)-N,N-diphenylamine
5 (BTPA) moieties (Fig. 1) to suppress the formation of crystal
6 in film through reducing the molecular rigidity and breaking
7 the molecular planarity. Comparing with triphenylamine,
8 BTPA moieties can be introduced simply with Wittig-honor
9 reaction, which reaction condition is much milder than
10 Ullmann reaction or carbon-carbon coupling reaction.^{22, 23} In
11 addition, the BTPA moiety has larger volume than
12 triphenylamine, which are benefit for suppressing
13 intermolecular stacking in solid states. With considering
14 above reasons, we chose BTPA moieties to modify the TPD
15 The molecular structures are shown in Fig. 1 and denoted as
16 TPD(BTPA)_n (n=1,2,4). The crystallization during the spin-
17 coating film forming process and the thermal stability of
18 these films are investigated by X-ray diffraction (XRD),
19 attenuated total reflectance fourier transform infrared
20 spectroscopy (ATR-FTIR) and differential scanning
21 calorimetry (DSC) measurements. The thermal stability
22 increases gradually with the increasing number of BTPA
23 moieties connected to the TPD. Notably, the spin-coating
24 film of TPD(BTPA)₄ can maintain amorphous even after
25 annealed at 110 °C for 48 h. At present, the reported HTM
26 films crystallized with annealing at < 95 °C for < 2 h, such as
27 N,N,N',N'-tetraphenylbenzidine (TPB), N,N,N',N'-tetra-*p*-
28 tolyl-benzidine (TTB), N,N'-di(naphthalene-1-yl)-N,N'-
29 diphenyl-benzidine (NPB), 9,10-(2-naphthyl)anthracene
30 (AND), 1,4-bis(phenyl-*m*-tolylamino) biphenyl (TPD), 1,4-
31 bis(benzothiazole-vinyl) benzene (BT) *et. al.*²⁴⁻³⁰



43 Fig. 1 Molecular structures of TPD(BTPA)_n compounds

44 The hole transport properties of as-synthesized HTMs
45 are evaluated in the solution processed OLEDs with the
46 structure of ITO/HTMs/Alq₃/LiF:Al. This structure with small
47 molecular HTMs (molecular weight < 6000 g mol⁻¹) has been
48 reported by many groups with maximum current efficiency
49 (CE_{max}) smaller than 5.7 cd A⁻¹, which are listed in Table 5.^{6, 11, 31-44}

50 In this work, the Device-TPD(BTPA)₄ can exhibit the
51 CE_{max} of 5.83 cd A⁻¹ at the operation current intensity larger
52 than 400 mA cm⁻². This CE_{max} is highest among the reported
53 small molecular OLED (molecular weight < 6000 g mol⁻¹) in
54 identical structure no matter fabricated with evaporation or
55 solution processing.^{6, 11, 31-44}

56 Results and Discussions

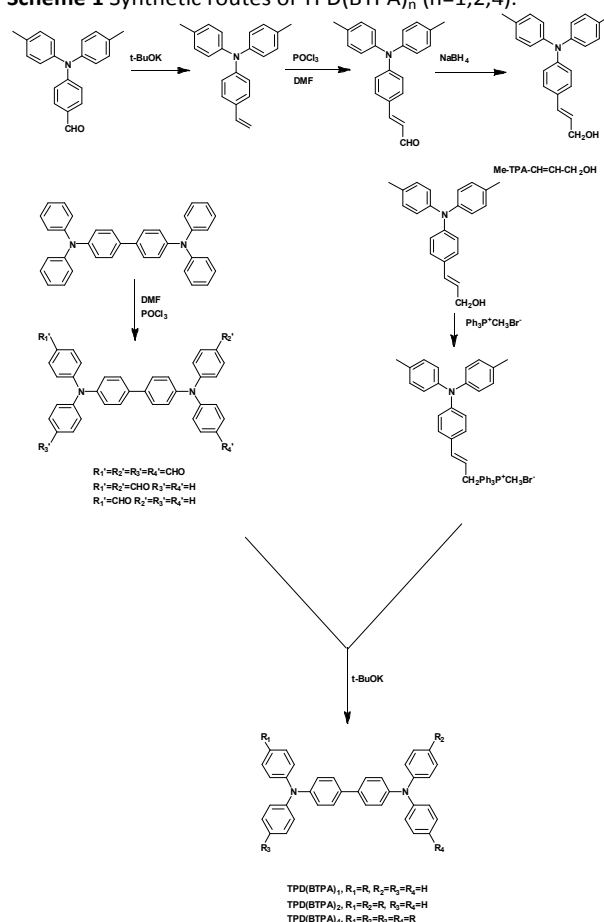
57 Synthesis and Characterizations

58 The TPD(BTPA)_n (n=1,2,4) are synthesized by formylation and
59 Wittig-Honor reactions starting with TPD (Scheme 1).⁴⁵

60 The BTPA moieties were synthesized from 4-(di-*p*-
61 tolylamino)benzaldehyde (Me-TPA-CHO) by formylation and
62 Wittig-Honor reactions. The total yield of 3-(4-(di-*p*-
63 tolylamino)phenyl)prop-2-en-1-ol (Me-TPA-CH=CH-CH₂OH)
64 was 92.0%. The aldehyde groups were introduced on the
65 TPD with different numbers. Then the BTPA moieties were
66 introduced on the TPD(CHO)_n (n=1,2,4) by Wittig-Honor
67 reaction. The yields were 72.3% (TPD(BTPA)₁), 68.2%
68 (TPD(BTPA)₂) and 63.4% (TPD(BTPA)₃), respectively. The
69 TPD(BTPA)_n (n=1,2,4) compounds are soluble in
70 methylbenzene, chlorobenzene, tetrahydrofuran and
71 chloroform, *etc.* The well-defined structures of all novel
72 compounds are adequately verified by ¹H NMR, mass
73 spectrometry and IR spectroscopy (see details in the ESI).

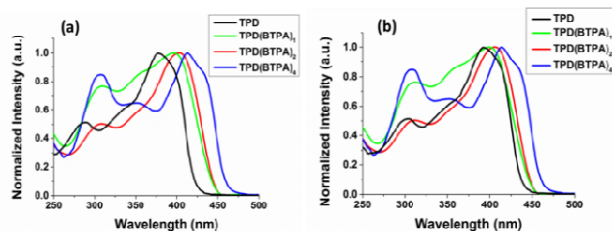
74 The decomposition temperatures (T_d , which correspond
75 to 5% weight loss) of TPD(BTPA)_n (n=0-4), recorded by
76 thermal gravity analysis (TGA), are 411 °C (TPD(BTPA)₁), 425 °C
77 (TPD(BTPA)₂), and 448 °C (TPD(BTPA)₄), respectively (Fig. S10,
78 Supporting Information). With the increase of *n* in
79 TPD(BTPA)_n, the T_d of as-synthesized HTMs increase
80 gradually.

81 Scheme 1 Synthetic routes of TPD(BTPA)_n (n=1,2,4).



1 Photophysical and Electrochemical Properties

2
3 UV-vis absorption spectra of TPD(BTPA)_n(n=0,1,2,4) are
4 shown in Fig. 2 and relative data are summarized in Table 1.
5 Cyclic voltammograms of TPD(BTPA)_n(n=0,1,2,4) are shown
6 in Fig. S11 (ESI).



16 Fig. 2 Normalized absorption spectra of TPD(BTPA)_n
17 (n=0,1,2,4) in chlorobenzene solution with concentration of
18 1.0×10^{-5} M (a) and spincoating films (b).

19
20 As shown in the Fig. 2a, the absorption peaks in the
21 wavelength region 280-310 nm can be assigned to the n- π
22 transition of the TPA moiety. The absorption peaks in the
23 region 375-450 nm can be assigned to the intramolecular
24 charge transfer (ICT) of π - π^* transition. There is an obvious
25 red shift of ICT peaks and decrease of energy gap (E_g) with
26 the increasing number of BTPA moiety. The absorption
27 spectrum of each TPD(BTPA)_n compound in solid state film
28 reveals no red-shift compared to that in chlorobenzene
29 solution, indicating that no significant aggregation or
30 crystallization occurs in the films of TPD(BTPA)_n(n=1,2,4).⁴⁶

31 As shown in Table 1, with the increase of number *n* in
32 TPD(BTPA)_n, the HOMO level increases from -
33 5.30eV(TPD(BTPA)₁) to -5.12eV(TPD(BTPA)₄), which exhibits
34 the HOMO level can be modified through changing the
35 number of BTPA moiety. The HOMO level of TPD(BTPA)₄
36 matches the work function of ITO (-4.80 eV) quite well,
37 which could benefit the charge injection without the
38 assistant of the normally-used hole injection layer (HIL)
39 poly(3,4-ethylene-dioxythiophene) poly(styrene sulfonate)
40 (PEDOT:PSS).⁴⁷

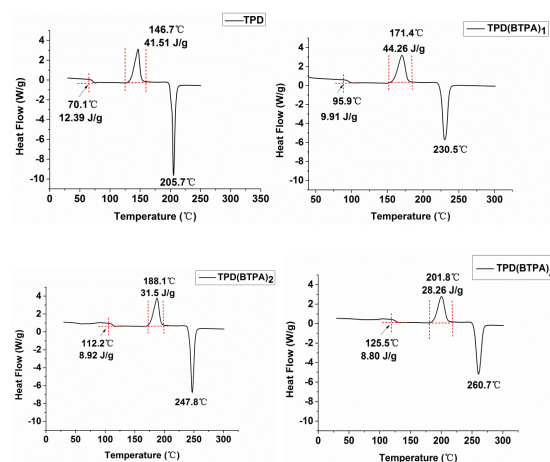
42 Table 1. The optical, thermal properties and energy levels of TPD(BTPA)_n (n=0,1,2,4)

	T_d ^{a)}	T_g ^{b)}	T_c ^{b)}	T_m ^{b)}	λ_{ITC} ^{c)}	E_g ^{d)}	HOMO ^{e)}	LUMO ^{e)}
	(°C)	(°C)	(°C)	(°C)	(nm)	(eV)	(eV)	(eV)
TPD	375	70.1	146.7	205.7	391	3.10	-5.30	-2.20
TPD(BTPA) ₁	411	95.9	17.4	230.5	399	2.94	-5.21	-2.27
TPD(BTPA) ₂	425	112.2	188.1	247.8	407	2.82	-5.16	-2.34
TPD(BTPA) ₄	448	125.5	201.8	260.7	415	2.73	-5.12	-2.39

53 ^{a)} Measured by TGA at a heating rate of 10 °C min⁻¹ under nitrogen atmosphere. ^{b)} T_g glass transition temperature, T_c
54 crystallization temperature, and T_m melt point measured by DSC according to the heat-cool-heat procedure (Fig. 3). ^{c)}
55 Intramolecular charge transfer peak of thin films. ^{d)} Optical energy gaps calculated from the absorption thresholds from UV-
56 Vis absorption spectra of chlorobezene solutions (1.0×10^{-5} M). ^{e)} Measured by cyclic voltammetry.

58 Thermal Properties of TPD(BTPA)_n

59
60 The thermal properties of TPD(BTPA)_n (n=0,1,2,4) are
61 investigated by the differential scanning calorimetry(DSC)
62 As shown in Fig. 3, the T_g , T_c and T_m of TPD(BTPA)_n
63 (n=0,1,2,4) increase gradually with the increasing number of
64 BTPA moieties (*n*). The T_g and T_c of TPD(BTPA)₄
65 than most of common used small molecular HTMs.²⁹⁻³⁴ The
66 corresponding enthalpies of crystallization are 41.51 Jg⁻¹
67 ¹(TPD), 44.26 Jg⁻¹(TPD(BTPA)₁), 31.5 Jg⁻¹(TPD(BTPA)₂) and
68 28.26 Jg⁻¹(TPD(BTPA)₄), respectively. This indicates that the
69 TPD and TPD(BTPA)₁ have higher crystallization tendency
70 than TPD(BTPA)₂ and TPD(BTPA)₄.⁶ Apparently, the BTPA
71 moieties showed a capability for improving thermal stability,
72 while only one BTPA moiety was not enough for changing
73 crystallization property noticeably.

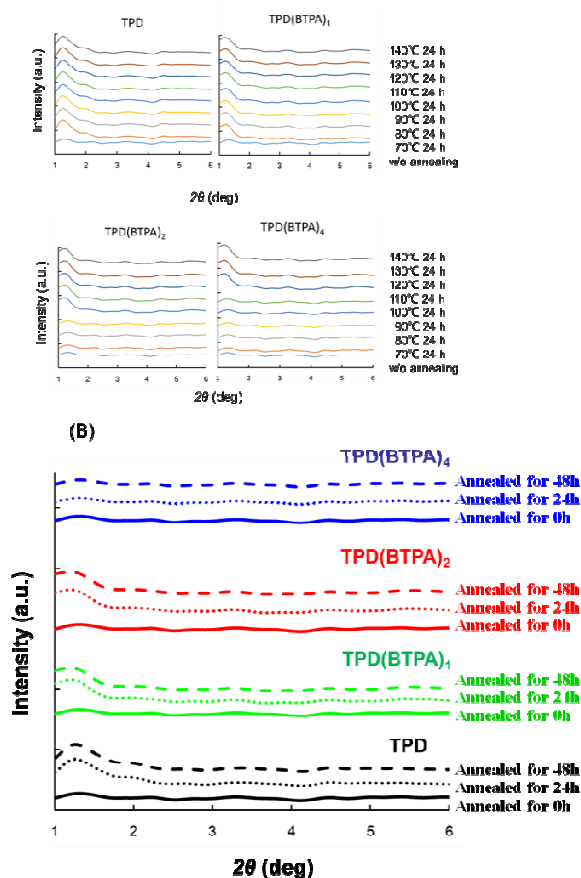


75
76
77 Fig. 3 DSC curves of TPD(BTPA)_n (n=0,1,2,4) selected from
78 the heating of second loop.

1 Crystallization of Spincoated Films

2
3 The amorphous films can improve charge injection and
4 transfer between different layers.⁴⁸⁻⁵⁰ It is important to find
5 out when the crystallization occurs. Therefore, we measured
6 the crystallinity of spincoated films before and after
7 annealing through X-Ray Diffraction(XRD) and Attenuated
8 Total Reflectance-Fourier Transformed Infrared
9 Spectroscopy (ATR-FTIR).

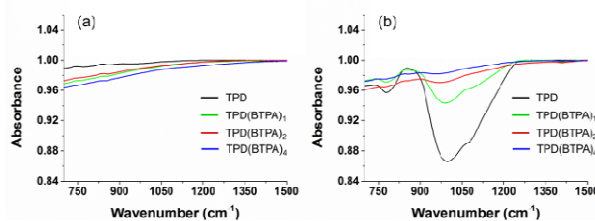
10 The XRD spectra of TPD(BTPA)_n films are shown in **Fig. 4**.
11 When the TPD(BTPA)_n (n=0,1,2,4) were spincoated on the
12 ITO substrate, the XRD patterns in the region of 0<2θ<5.0°
13 were same as that of ITO substrate, which indicating that all
14 these spincoated films were amorphous. The diffraction
15 peaks (2θ ≈ 1.5°) can be observed in TPD and TPD(BTPA)₁
16 when these films were annealed at 70 °C for 24 h. The
17 diffraction peaks (2θ ≈ 1.5°) in TPD(BTPA)₂ and TPD(BTPA)₄
18 films appeared at annealing temperature of 100 °C and 120 °C,
19 respectively. As shown in **Fig. 5(B)**, for the TPD(BTPA)₄ film,
20 the XRD pattern maintained unchanged even annealed at
21 110 °C for 48 h.



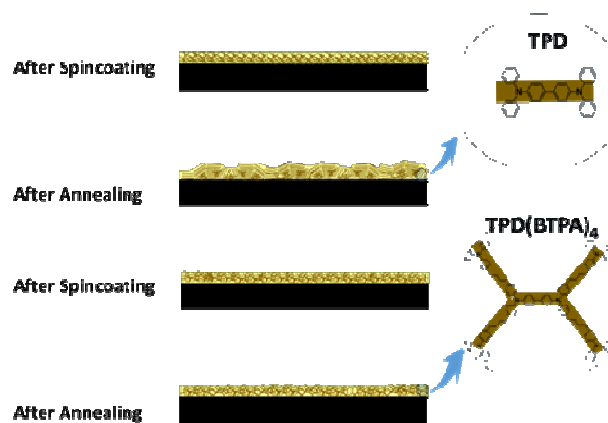
22 **Fig. 4** X-ray diffraction patterns of films on ITO glass
23 substrate annealed from 70-140 °C for 24 h (a); annealed at
24 110 °C for 0-48 h(b)

25
26 The crystallinity were confirmed directly by ATR-FTIR
27 measurement.⁵¹ As shown in **Fig. 5**, for spincoated films of

28 TPD and TPD(BTPA)₁, a broad band in the wavenumber
29 region of 900-1200 cm⁻¹, and a small band in the
30 wavenumber region of 700-800 cm⁻¹ generated after
31 annealing. The broad band can be assigned to the in-plane
32 vibration of benzene.⁵² This phenomenon generate from the
33 change of optical property after crystallization. The change
34 of ATR-FTIR spectra for TPD(BTPA)₂ and TPD(BTPA)₄ films
35 before and after annealing at 100 °C are unobvious, which
36 mean the TPD(BTPA)₂ and TPD(BTPA)₄ films maintained
37 amorphous. For most of reported small molecular HTMs,
38 such as TPB, TTB, NPB, AND, TPD and BT, these films cannot
39 maintain amorphous form with annealing > 80 °C less than 2
40 h.²⁹⁻³⁴



41
42 **Fig.5** ATR-FTIR spectra of TPD compounds before(a) and
43 after annealing(b).



44
45 **Fig. 6** Crystallization process in spincoated films.

46
47 All the results above indicate that the crystallization
48 capability is suppressed with BTPA moieties. The
49 crystallization process does not happen during spincoating
50 process. Instead, it occurs after the film-forming process. The
51 possible process is shown in **Fig. 6**.

52 All the spincoated films are amorphous before
53 annealing. As shown in **Fig. 6**, we discuss the two extreme
54 situations: TPD (crystalline) and TPD(BTPA)₄ (amorphous). In
55 the case of TPD, after spincoating the TPD molecules deposit
56 on the substrate randomly and the TPD film is amorphous
57 accordingly. While, the TPD molecule tends to stack because
58 of its planarity molecular structure, low T_g and T_c , as well as
59 the large change of enthalpies after crystallization. Then, the
60 orientated aggregation (crystallization) occurs, which will
61 break the homogenous TPD films.

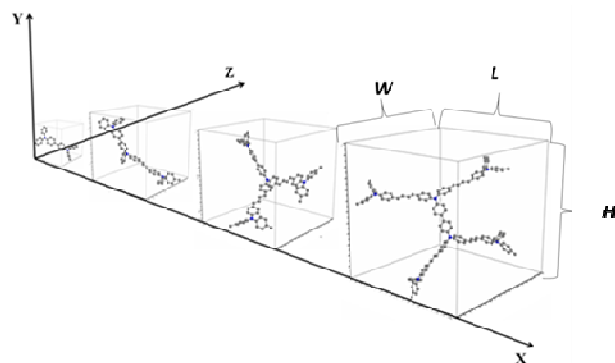
1 In the case of TPD(BTPA)₄, the film maintains
2 amorphous after annealing. Compared with TPD, the
3 molecular structure of TPD(BTPA)₄ is nonplanar. In addition,
4 the TPD(BTPA)₄ has higher T_g , T_c and smaller change of
5 enthalpies after crystallization. These prevent the orientated
6 aggregation (crystallization) in TPD(BTPA)₄ after annealing.
7 The crystallization property of TPD(BTPA)₁ and TPD(BTPA)₂
8 should be between that of TPD and TPD(BTPA)₄.

10 Molecular Geometry

12 One of the most important roles of BTPA moiety is breaking
13 the planarity of TPD. In this work, the molecular geometry
14 was applied to estimate the change of planarity. First, the
15 molecular geometries of TPD(BTPA)_n (n=0,1,2,4) were
16 optimized with Gaussian 03 program.⁵³ Then the cartesian
17 coordinates of all the atoms in each molecule were obtained
18 from above step. We put the molecule into a regular
19 hexahedron as shown in Fig. 7.

20 The L , W , H and volume of regular hexahedron are listed
21 in Table 2. Apparently, the TPD molecule is much close to a
22 plate. With the increasing BTPA moieties, the molecules of
23 TPD(BTPA)_n (n=1,2,4) are approach to cubes. This indicated
24 that, beside increasing the molecular volume, the BTPA
25 moieties can break the molecular planar effectively. This
26 change of molecular geometry greatly affect the thermal
27 stability of TPD(BTPA)_n, which leads to the amorphous films
28 of TPD(BTPA)₄ even after annealing at 110 °C for 48 h.

29



30 Fig. 7 Molecular geometry of TPD(BTPA)_n (n=0,1,2,4) in a
31 regular hexahedron with length, width and height of L , W
32 and H , respectively.

33

34 Table 2. Geometry Parameters of TPD(BTPA)_n (n=0, 1, 2, 4)

	L^a	W^a	H^a	Volume ^{b)}	$L:W:H^c$
TPD	15	6	16	1440	2.5:1.0:2.7
TPD(BTPA) ₁	14	16	25	5600	1.0:1.1:1.8
TPD(BTPA) ₂	14	21	36	10584	1.0:1.5:2.6
TPD(BTPA) ₄	38	25	36	34200	1.52:1.0:1.44

35 ^{a)} Estimated by the cartesian coordinates of all the atoms after
36 geometry optimized with Gaussian 03. ^{b)} Volume = $L \times W \times H$. ^{c)}

37 Normalized with minimum value of L, W and H ; all the units are
38 a.u..

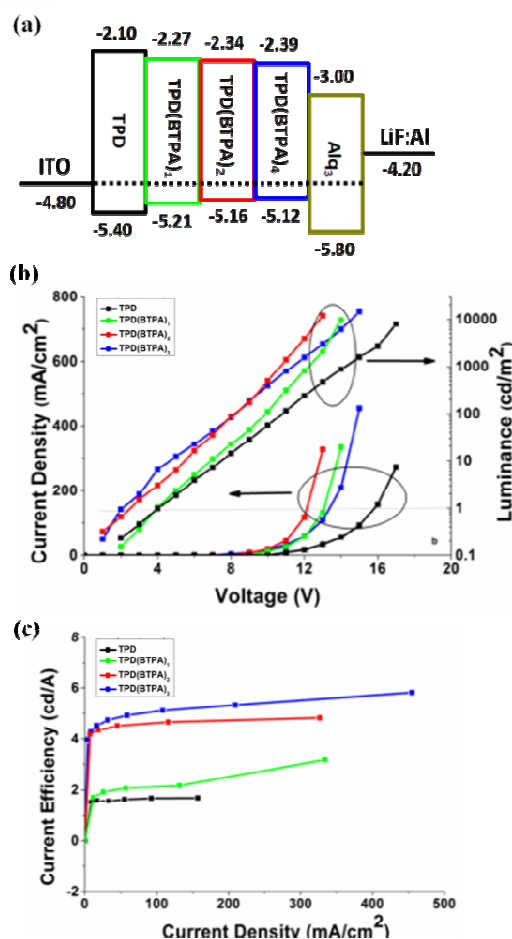
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40 Application in OLEDs

41

42 One role of BTPA moiety is increasing the molecular volume
43 to suppress crystallization in films and improve the thermal
44 stability. Another role is increasing the molecular
45 conjugation by introducing the butadiene units. As discussed
46 above, with the increasing number of BTPA moieties, the
47 HOMO levels of as-synthesized HTMs slightly increases.

48 As the HOMO levels of TPD(BTPA)_n (n=0-4) are in the
49 range of -5.12~-5.40 eV which are very close to the HOMO
50 level of commonly-used hole injection material PEDOT:PSS (-
51 5.00 eV),⁵⁴ we fabricate double-layer OLEDs using
52 TPD(BTPA)_n as hole injection/transport double-functional
53 layers, Alq₃ as electron transport and emission layers, with
54 the device structure: ITO/TPD(BTPA)_n (200 nm)/Alq₃ (70
55 nm)/LiF:Al (120 nm). The current-voltage-
56 luminance (J - V - L) characteristic curves and LE - J of these
57 OLEDs are shown in Fig. 8, the parameters are listed in Table
58 3.



59

60 Fig. 8 OLED structures(a), J - V - L curves (b) and J - η curves(c)

As shown in Fig. 8(b) and Table 3, the turn-on voltage (V_{on}) of Device-TPD and Device-TPD(BTPA)₁ are the same, despite the HOMO level of TPD(BTPA)₁ (-5.21 eV) is much closer to the work function of ITO (-4.80 eV) than TPD (-5.40 eV). However, compared to Device-TPD, the V_{on} reduces 28% (Device-TPD(BTPA)₂) and 38% (Device-TPD(BTPA)₄). This indicated the smaller difference between ITO work function and HOMO level of TPD(BTPA)_n are beneficial to hole injection.

Table 3. Electroluminescence characteristics of OLEDs

Device	V_{on} ^{a)} (V)	L_{max} ^{b)} (cd m^{-2})	CD ^{b)} (mA cm^{-2})	CE ^{c)} (cd A^{-1})	μ_h ^{d)} ($\times 10^{-5} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$)
TPD	5.0	8152 (17.0 V)	272	2.16	140
TPD(BTPA) ₁	5.0	9590 (13.9 V)	334	3.17	24
TPD(BTPA) ₂	3.6	12281 (13.1 V)	327	4.83	15
TPD(BTPA) ₄	3.1	14446 (15.2 V)	455	5.83	9

^{a)} Turn-on voltage: the voltage at the brightness of 1 cd m^{-2} ;

^{b)} Maximum brightness and corresponding voltage in the bracket;

^{c)} Maximum current efficiency;

^{d)} Measured in hole-only devices (structure: ITO/HTMs (~1 μm)/Al (120 nm)). Hole mobilities are determined by time-of-flight (TOF) method²⁹, details see ESI Fig. S12.

From the Table 3, compared with Device-TPD, the maximum brightness (L_{max}) increase 20% (Device-TPD(BTPA)₁), 50% (Device-TPD(BTPA)₂) and 80% (Device-TPD(BTPA)₄); the maximum current efficiency (CE_{max}) increase 50%, 120% and 170%, respectively. The LUMO levels of TPD(BTPA)_n ($n=0-4$) are in the range of -2.10~ -2.39 eV, which are higher than the LUMO level of Alq₃ and it means that the TPD(BTPA)_n ($n=0-4$) layer can play the role of electron blocking.

Hole mobilities of TPD(BTPA)_n ($n=0,1,2,4$) decreased with increasing number of BTPA moieties n . This mainly result from the suppression of crystallization by BTPA moieties. The electron mobility (μ_e) of Alq₃ was reported to be $\sim 1.1-2.3 \times 10^{-5} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$.²⁹ The equilibrium of electron and hole transport in device-TPD(BTPA)₄ resulted higher CE than other OLEDs.

The most interesting phenomenon is that the CE increases with higher operation current in the Device-TPD(BTPA)₁, Device-TPD(BTPA)₂, and Device-TPD(BTPA)₄. This should result from the outstanding thermal stability of the TPD(BTPA)_n ($n=2,4$) films which can maintain amorphous even at high operation current.

To further investigate the hole injection/transport properties of TPD(BTPA)₄, we compare the performance of OLEDs with and without PEDOT:PSS layer, which are denoted as Device-PP-TPD(BTPA)₄ (structure: ITO/PEDOT:PSS

(100nm)/TPD(BTPA)₄ (200 nm)/Alq₃ (70 nm)/LiF (0.5 nm)/Al (120 nm) and Device-TPD(BTPA)₄ (device structure: ITO/TPD(BTPA)₄ (200 nm)/Alq₃ (70 nm)/LiF (0.5 nm)/Al (120 nm)), respectively. The device structures, current-voltage-luminance (J - V - L) characteristic curves and current-efficiency (J - η) curves are shown in Fig. 9, parameters are listed in Table 4.

As reported, the PEDOT:PSS normally applied to improve hole injection because of its HOMO level closing to the work function of ITO. However, the Device-PP-TPD(BTPA)₄ shows a higher V_{on} (3.1 V) and a lower CE_{max} (4.48 cd A^{-1}) than Device-TPD(BTPA)₄. From Fig. 9 (c), it can be found that with the increasing current intensity, the efficiency of the Device-PP-TPD(BTPA)₄ reduces obviously. On the contrary, the Device-TPD(BTPA)₄ remains stable.

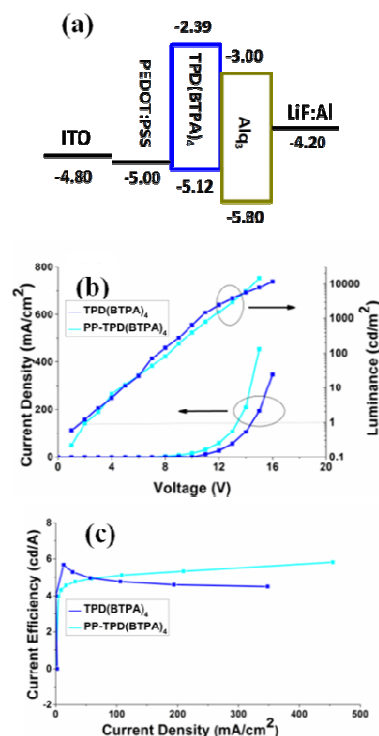


Fig. 9 OLED structures (a), J - V - L curves (b) and J - η curves (c)

Table 4. Electroluminescence characteristics of OLEDs

Device	V_{on} ^{a)} (V)	L_{max} ^{b)} (cd m^{-2})	CD ^{c)} (mA cm^{-2})	CE ^{d)} (cd A^{-1})
TPD(BTPA) ₄ ^{e)}	3.1	14446 (15.2)	455	5.83
PP-TPD(BTPA) ₄ ^{f)}	3.8	12280 (16.1)	348	4.48

^{a)} Turn-on voltage: the voltage at the brightness of 1 cd m^{-2} ; ^{b)}

Maximum brightness; ^{c)} Current efficiency at the maximum

brightness; ^{d)} Maximum current efficiency;

1 It has been reported that during spin-coating the acidity
2 of PEDOT:PSS colloidal solution can corrode ITO to dissolve
3 some In^{3+} . The In^{3+} will make the PEDOT:PSS interface
4 unstable

5 and obstruct the hole injection, which will diffuse to emitting
6 layer to form a quenching center when devices operating at
7 high current. This should be the reason for decrease of CE_{max}
8 at higher current density in Device-PP-TPD(BTPA)₄.⁵⁵⁻⁵⁹

9 In Device-TPD(BTPA)₄, both the performance and the
10 stability at high current density of OLEDs have been
11 improved. The improvement of OLED performance at high
12 operation currents should be result from the combine effects
13 of outstanding thermal stability of hole transport layer and
14 balance of electron-hole transporting in device. This confirms
15 that the TPD(BTPA)_n ($n>1$) can be applied as hole
16 injection/transport di-functional material to improve the
17 performance and stability of OLEDs, as well as simplify the
18 fabrication process of solution-processing OLEDs.

19 The HTMs applied in solution-processing OLEDs with
20 identical structure are reported.^{6, 11, 31-44} The molecular
21 formula (MF), molecular weight (MW), HOMO level, LUMO
22 level, energy gap of reported HTMs and corresponding
23 parameters of OLEDs are listed in **Table 5**. All the molecular
24 structure are listed in **ESI Fig. S13**.

25 **Table 5.** Reported HTMs for solution-processing OLEDs with identical structure

27	28	29	30	31	32	33	34	35	36	37	38	39	40
Compounds	MF	MW	HOMO (eV)	LUMO (eV)	E_g (eV)	Device Structure	V_{on} (V)	CE (cd A^{-1})	$J_{90\%}$ (mA cm^{-2})				
^{a)} DT2 ^[6]	$\text{C}_{432}\text{H}_{300}\text{N}_{22}$	5799	-5.22	-2.60	2.62	ITO/PEDOT:PSS/DT2/Alq3/LiF:Al	2.9	2.36	5				
^{a)} G3F2 ^[34]	$\text{C}_{242}\text{H}_{212}\text{N}_{14}$	3316	-5.4	-2.19	3.21	ITO/PEDOT:PSS/G3F2/Alq3/LiF:Al	2.6	5.63	123				
^{a)} TPD(BTPA) ₄ ^(c)	$\text{C}_{123}\text{H}_{112}\text{N}_6$	1782	-5.12	-2.39	2.73	ITO/TPD(BTPA) ₄ /Alq3/LiF:Al	3.1	5.83	Unobservable				
^{a)} G3C ^[36]	$\text{C}_{97}\text{H}_{77}\text{N}_7$	1341	-5.37	-2.01	3.36	ITO/PEDOT:PSS/TPD(BTPA) ₄ /Alq3/LiF:Al	3.8	4.48	168				
^{a)} T4C ^[35]	$\text{C}_{96}\text{H}_{85}\text{N}_5$	1309	-5.15	-1.91	3.24	ITO/PEDOT:PSS/G3C/Alq3/LiF:Al	3	5.11	103				
^{a)} FC ^[37]	$\text{C}_{85}\text{H}_{97}\text{N}_3$	1161	-5.21	-2.39	2.82	ITO/PEDOT:PSS/T4C/Alq3/LiF:Al	2.5	5.07	160				
^{b)} TECEB ^[31]	$\text{C}_{54}\text{H}_{45}\text{N}_3$	735	-5.20	-2.40	2.80	ITO/PEDOT:PSS/FC/Alq3/LiF:Al	5.6	3.2	155				
^{b)} FTPD7 ^[30]	$\text{C}_{53}\text{H}_{44}\text{N}_2$	708	-5.80	-2.12	3.68	ITO/TECEB/Alq3/Mg:Ag	3.5	3.27	120				
^{a)} TPD ^[11]	$\text{C}_{36}\text{H}_{28}\text{N}_2$	488	-5.40	-2.10	3.30	ITO/FTPD7/Alq3/LiF:Al	6.5	2.18	\				
						ITO/TPD/Alq3/LiF:Al	2.0	3.67	200				

40 ^{a)} Spin-coated HTMs; ^{b)} Vacuum-deposited HTMs; ^{c)} As-synthesized HTM in this work

43 As shown in **Table 5**, the Device-TPD(BTPA)₄ shows the
44 highest CE_{max} which is far beyond other reported small
45 molecular HTMs ($Mw < 6000$) with identical structure no
46 matter fabricated by vacuum deposition or spin-coated.<sup>6, 11,
47 31-44</sup> In addition, the efficiency roll-off is unobservable in
48 device applying TPD(BTPA)_n ($n=1,2,4$) as hole
49 transport/injection bi-functional material, which confirmed
50 the outstanding operation stability even at large operation
51 current. At present, only the 1,2,3,4,5,6-hexakis(9,9-dihexyl-
52 9H-fluoren-2-yl)benzene T3($CE_{max} = 6.45 \text{ cd A}^{-1}$) showed
53 slightly higher efficiency than Device-TPD(BTPA)₄.⁴⁰ However,
54 the MW of T3 is much larger than TPD(BTPA)₄ (>4 times). Not
55 a mention the V_{on} of Device-T3 (5.5 V) is much higher than
56 Device-TPD(BTPA)₄ (3.1 V).⁴⁰

58 Conclusions

59 In this work, the novel HTMs TPD(BTPA)_n ($n=1,2,4$) have been
60 designed and synthesized. The BTPA moieties are introduced
61 into TPD to improve thermal stability and suppress
62 crystallization in spincoated films. The thermal stability of
63 TPD(BTPA)_n ($n=0,1,2,4$) have been investigated by DSC,
64 which shows gradual increases of T_g , T_c and T_m with the
65 increasing number of TBPA moieties. The spincoated film of
66 TPD(BTPA)₄ maintained amorphous form even with 110°C,
67 48 h annealing which confirmed by XRD and ATR-FTIR. The
68 OLEDs with TPD(BTPA)_n ($n=0,1,2,4$) as HIL and HTL showed
69 an improvement of performance with increasing the number
70 of TBPA moieties. The BTPA moieties can improve the
71 stability of OLED operated with high current. The OLED with
72 TPD(BTPA)₄ showed the highest CE_{max} compared with
73 reported small molecular ($Mw < 6000$) HTMs with identical
74 structure no mater solution processing or vacuum deposition.

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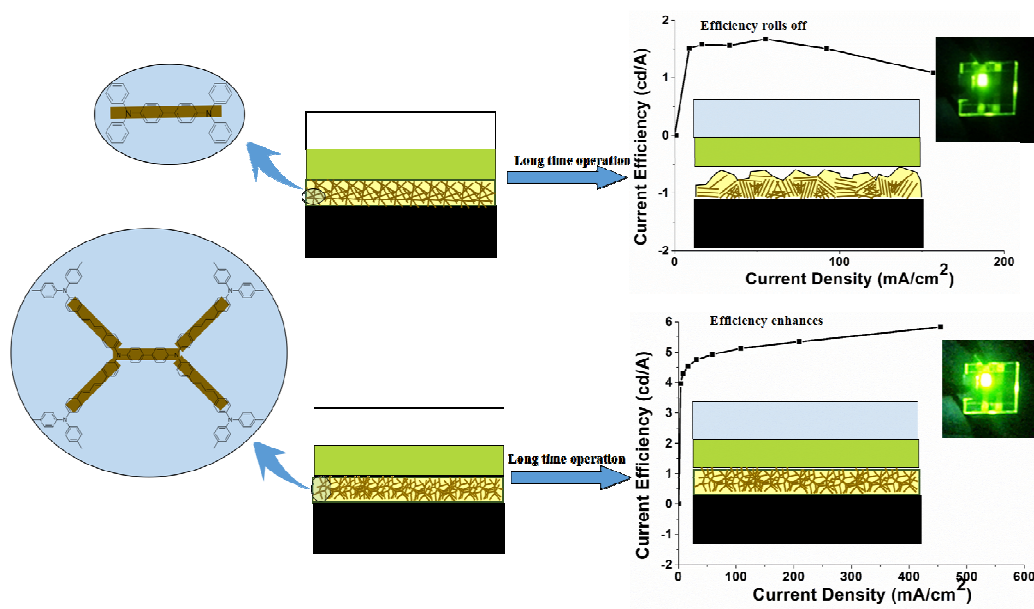
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TPD(BTPA)₄ can improve the stability of OLED operated with high current and can achieve the one of the highest CE_{max} (5.83 cd A^{-1}) compared with reported small molecular ($M_w < 6000$) HTMs in OLEDs with identical structure no matter solution processing or vacuum deposition.